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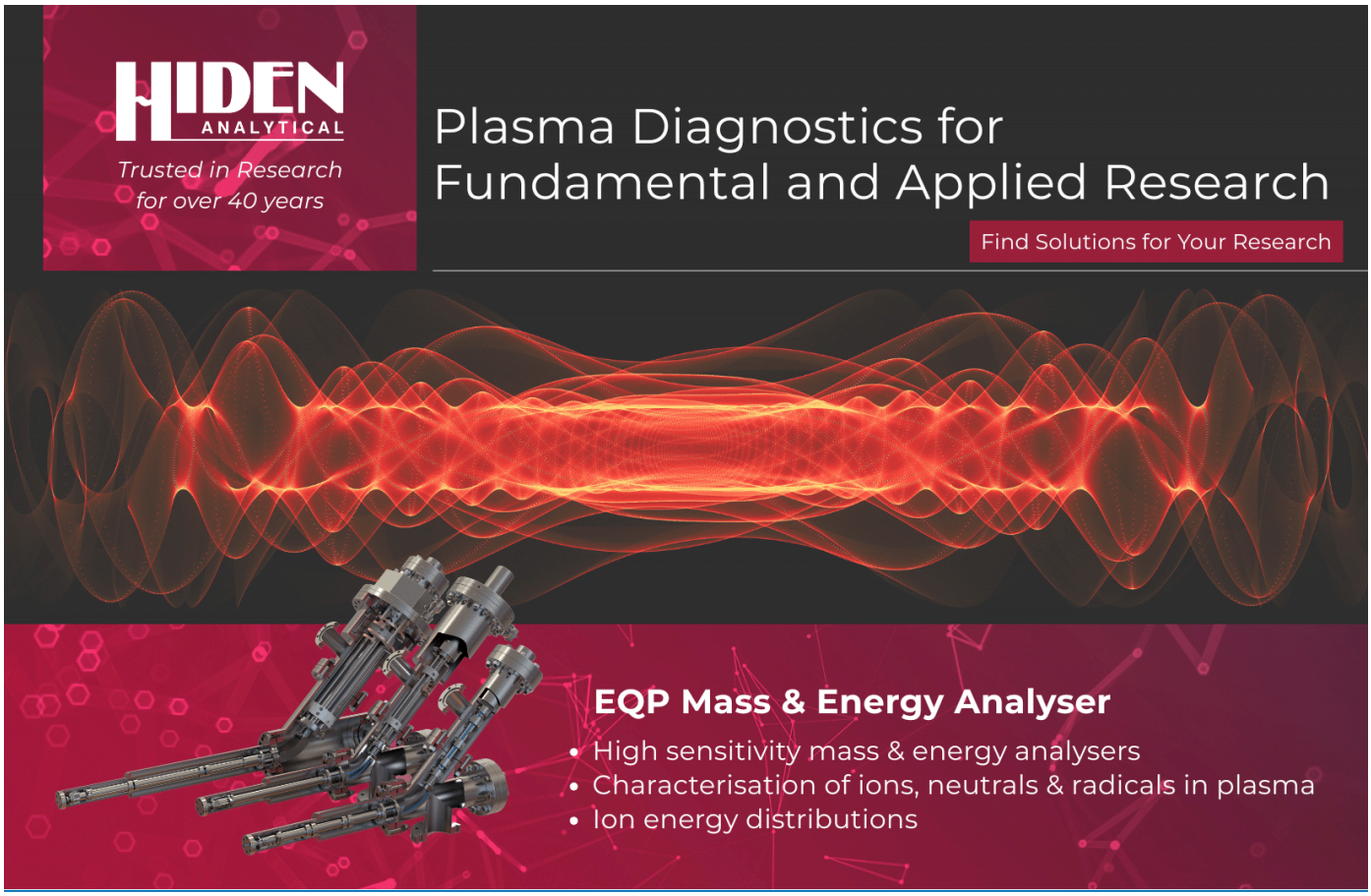

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CORRIGENDUM: Control of photoresist etch rate via a gradient magnetic field in biased inductively coupled plasma (2025 *Plasma Sources Sci. Technol.* **34** 075008)

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In the original version of this article, the Acknowledgment section on p. 11 contains an incorrect grant number (RS-2023-00237362). The grant number should be revised to RS-2023-00237543. Therefore, the Acknowledgment should be revised as below;

Acknowledgment

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This correction does not alter the contents of this article, including the results, discussions, and conclusions.

Data availability statement

No new data were created or analysed in this study.

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